

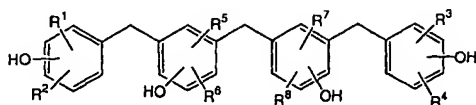
AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

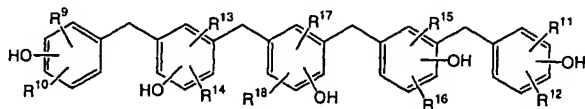
Claim 1 (currently amended): A positive photoresist composition comprising:

- (A) an alkali-soluble resin;
- (B) a photosensitizer comprising a quinonediazide ester between a naphthoquinonediazidosulfonic acid compound and [[at least one of a compound represented by following Formula (I):



(I)

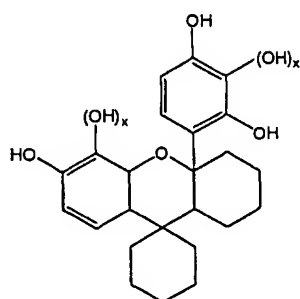
wherein R¹, R², R³, R⁴, R⁵, R⁶, R⁷ and R⁸ are each independently a hydrogen atom or an alkyl group having from 1 to 3 carbon atoms, and]] a compound represented by following Formula (II):



(II)

wherein R^9 , R^{10} , R^{11} , R^{12} , R^{13} , R^{14} , R^{15} , R^{16} , R^{17} and R^{18} are each independently a hydrogen atom, an alkyl group having from 1 to 3 carbon atoms or a cyclohexyl group; and

(C) a sensitizer comprising at least one of compounds represented by following Formula (III):

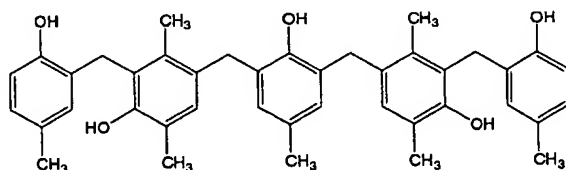


(III)

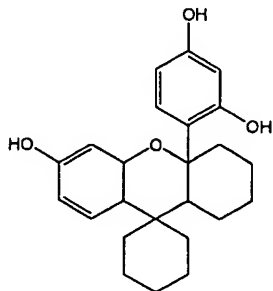
wherein x is 0 or 1.

Claim 2 (cancelled).

Claim 3 (original): The positive photoresist composition according to claim 1, wherein the compound represented by Formula (II) is a compound represented by the following formula:



Claim 4 (original): The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:



Claim 5 (original): The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:

